



Advances in Photodetecting Materials, Devices and Applications

Guest Editor:

Dr. Zhanfeng Huang

School of Microelectronics
Science and Technology, Sun
Yat-sen University Zhuhai
Campus, Guangdong 519082,
China

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Message from the Guest Editor

Dear Colleagues,

Photodetection, which converts optical signals into electrical signals, is an irreplaceable source of information. Photodetectors with different response spectra have been used in various applications, such as imaging, communication, measurement, monitoring, etc.

To meet the growing demand for higher figure-of-merit parameters and new application scenarios, it is crucial to improve the performance of photodetectors through the development of new materials, novel device design, and exploration of new application. Accordingly, this Special Issue seeks to showcase research papers and review articles on (1) the methodology of synthesizing emerging photodetecting materials, e.g., perovskites, polymers, novel two-dimensional materials, and quantum dots; (2) photodetectors with novel structures, physics, and high figure-of-merit parameters; (3) demonstration of new applications of photodetectors.

We look forward to receiving your submissions.





Editor-in-Chief

Message from the Editor-in-Chief

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Micromachines Editorial Office
MDPI, St. Alban-Anlage 66
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